VALQUA Semiconductor Industry Products

FLUORITZ®-OR

High Performance FFKM

Product Overview

FLUORITZ[®]-OR is a high purity, low particle, low outgassing material that improves upon radical and ozone resistance when compared to the conventional perfluoroelastomer. Especially suited for cleaning environments with NF3 gas + remote plasma source and ozone processes, expect FLUORITZ[®]-OR to extend seal life while reducing particle generation.

Additionally, its excellent mechanical strength makes the material well suited for dynamic locations, and FLUORITZ [®]-OR is also available as a bonded seal.

Characteristics

- Excellent resistance to radicals and ozone
- Low metal content for particle reduction
- Low outgassing
- Mechanical strength for dynamic applications



Uses

Process

Plasma Etch / CVD / ALD / ALE / Remote Fluorine Plasma Clean, etc.

Applications

Chamber lid / Isolator valve / Gas inlet / Gate etc.

Material Properties

| Color | Black |
|--|-------|
| Hardness ^{*1} (Shore A) | 82 |
| Tensile Strength ^{*2} (MPa) | 16.3 |
| Elongation ^{*2} (%) | 173 |
| 100% Modulus ^{*2} (MPa) | 8.4 |
| Compression Set ^{*3} (%) | 19 |
| Maximum Temperature ^{*4} (°C) | 300 |

Compression Set: 25% compression at 200°C for 72 hours Values above are actual measurements, not specifications *1 Test Sample: Sheet *2 Test Sample: Dumbbell

*1 Test Sample: Sheet *2 Test Sample: Dumbbell *3 Test Sample: AS568-214 O-Ring *4 Proprietary test method

Contact Us

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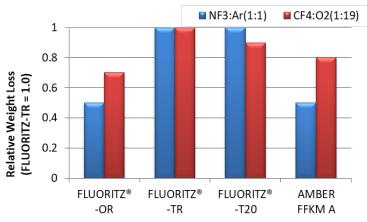
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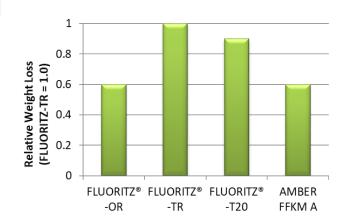
Additional information

FLUORITZ[®]-OR

Ozone Resistance

Performance Data

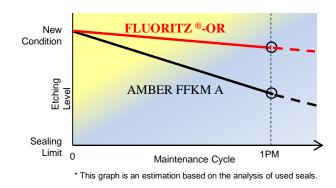




Radical Resistance

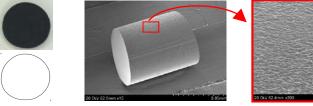
Example of Use

- Example of use at a major fab in Japan
- Process: Etching/Ashing
- Process Gas: Etching $SF_6 + O_2/Ashing CF_4 + O_2$
- O-ring Size: AS568-280
- Duration:1 PM Cycle



Longer lifetime compared to AMBER FFKM A

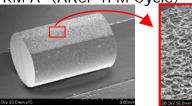
■FLUORITZ [®]-OR (After 1PM Cycle)





■AMBER FFKM A (After 1PM Cycle)





Remarkable etching is confirmed.